

# AlGaInAs/InP coupled-circular microlasers

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AlGaInAs/InP coupled-circular microlasers with radius of 10- and 2- $\mu\text{m}$  width middle bus waveguide are fabricated by photolithography and inductively coupled plasma etching techniques. Room-temperature continuous-wave single-mode operation is realized with an output power of 0.17 mW and a side-mode suppression ratio of 23 dB at 45 mA. A longitudinal mode interval of 11 nm is obtained from the lasing spectra, and mode  $Q$  factor of  $6.2 \times 10^3$  is estimated from 3-dB width of a minor peak near the threshold current. The mode characteristics are simulated by finite-difference time-domain technique for coupled-circular resonators. The results show that, in addition to the coupled modes, high-radial-order whispering gallery modes with travelling wave behaviors can also have high  $Q$  factors in the coupled-circular resonators with a middle bus waveguide.

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Semiconductor microlasers with whispering gallery modes (WGMs) have attracted great attention in the past two decades. Among these microlasers, microdisk laser with an ultrasmall cavity volume is the most common semiconductor microlaser<sup>[1]</sup>. However, directional emission is greatly limited in a circular-symmetry microdisk laser. Asymmetric circular resonators<sup>[2]</sup>, spiral-shaped micropillars<sup>[3]</sup>, elliptical microdisks<sup>[4]</sup>, limaçon-shaped chaotic microcavities<sup>[5]</sup>, and microdisk resonators evanescently coupled to a bus waveguide<sup>[6]</sup> have been investigated to realize directional emission microlasers. Recently, we realized continuous-wave (CW) electrically injected AlGaInAs/InP microcircular lasers at room temperature, which were connected to one or two output waveguides for directional emission<sup>[7,8]</sup>.

Recently, mode radiation loss for microdisk resonators with pedestals was investigated by finite-difference time-domain (FDTD) technique<sup>[9]</sup>. For a circular microresonator connected to an output waveguide, the high- $Q$  confined modes are usually the coupled modes between two WGMs with standing mode field patterns. However, high- $Q$  confined modes with travelling mode field patterns are interesting for potential optical signal processing. Coupled-circular microresonators with a middle output waveguide can have high- $Q$  coupled modes between WGMs, which can be predicted by FDTD technique<sup>[10]</sup>. Furthermore, optical bistable operation has been observed due to the transverse and degenerate mode competition in a coupled-circular GaInAsP/InP microlaser with a radius of 20  $\mu\text{m}$ <sup>[11]</sup>. In this letter, we report the fabrication and characteristics of AlGaInAs/InP coupled-circular microlasers with a radius of 10  $\mu\text{m}$ . Single-transverse-mode operation is observed with evident angular (longitudinal) mode structure in the lasing spectra, and mode  $Q$  factor of  $6.2 \times 10^3$  is estimated from the full-width at half-maximum (FWHM) of a minor mode near the threshold current.

The coupled-circular microlasers were fabricated using a common edge-emitting AlGaInAs/InP laser wafer.

The active region of the laser wafer comprised six compressively strained  $\text{Al}_{0.24}\text{GaIn}_{0.71}\text{As}/\text{Al}_{0.44}\text{GaIn}_{0.49}\text{As}$  quantum wells sandwiched by 60-nm undoped graded AlGaInAs and 60-nm doped AlGaInAs cladding layers. The thicknesses of the quantum wells and barrier layers were 6 and 10 nm, respectively. The upper layers were p-InP and p<sup>+</sup>-InGaAs contacting layers with the total thickness of 1920 nm. The technique process used for fabricating the microlasers is similar to that in Ref. [11]. First, an 800-nm  $\text{SiO}_2$  was deposited by plasma-enhanced chemical vapor deposition (PECVD) onto the laser wafer, after which the coupled-circular resonator patterns were transferred onto the  $\text{SiO}_2$  layer using standard photolithography and inductively coupled plasma (ICP) etching techniques. Next, the laser wafer was etched approximately 5.5  $\mu\text{m}$  using ICP technique with the patterned  $\text{SiO}_2$  as masks. Figure 1(a) shows the scanning electron microscope (SEM) image of a coupled-circular microresonator, whereas Fig. 1(b) is the detail SEM image of the tangentially coupled region. After the ICP etching process, a chemically etching process was used to improve the smoothness of the etched side walls. The residual  $\text{SiO}_2$  hard masks on the microcylinders were etched using diluted HF solution. A 450-nm  $\text{SiO}_2$  insulating layer was deposited onto the wafer, and the  $\text{SiO}_2$  layer on the top of circular resonators was etched using ICP etching process again for electrical injection. Finally, Ti-Pt-Au and Au-Ge-Ni were used as p-contact and n-contact metals, respectively.

After cleaving over the bus waveguide, the coupled circular microlasers were tested at room temperature

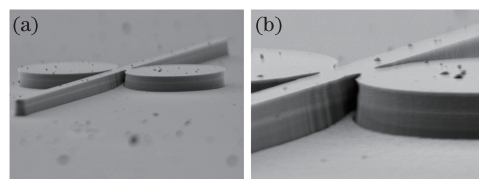


Fig. 1. SEM images of a coupled-circular resonator.

without controlling temperature. The output power measured by an integrated sphere and applied voltage versus CW injection current for a coupled-circular microlaser with the circular radius of  $10\ \mu\text{m}$  and the bus waveguide width of  $2\ \mu\text{m}$  are plotted in Fig. 2. The output powers were 0.17 and 0.29 mW at the injection currents of 45 and 100 mA, respectively. Series resistor of  $7\ \Omega$  was estimated by dividing the variation of the voltage to that of the injection current around the threshold current of 20 mA.

The laser spectra at CW injection currents of 25, 45, and 75 mA for the coupled-circular microlaser are plotted in Fig. 3. Two main modes with mode wavelengths of 1549.9 and 1561.0 nm, with an intensity difference of approximately 6 dB, can be observed in Fig. 3(a). The other minor modes were 20 dB less than the main mode at 1561.0 nm. Single-mode operation with side-mode suppression ratios of 23 and 22 dB was reached at the injection currents of 45 and 75 mA, respectively, as shown in Fig. 3(b). The mode wavelength increased from 1572.1 to 1574.9 nm as the injection current increased from 25 to 75 mA, corresponding to the temperature rise of 28 K as the mode wavelength varied with the temperature at 0.1 nm/K. The lasing modes were at the wavelengths of 1561.9 and 1574.9 nm when the injection current was 45 and 75 mA, respectively. This phenomenon is caused by the increase of the peak wavelength of the gain spectrum with the temperature. Comparing with the optical bistability in the coupled-circular microlaser caused by the transverse and degenerate mode competition in Ref. [11], we have single-transverse-mode operation, as shown in the laser spectra in Fig. 3.

Assuming the wavelength intervals is the angular (longitudinal) mode interval and one period of the mode light path is the perimeter of the circular resonator, we can fit the longitudinal mode interval by  $\delta\lambda = \lambda^2/2\pi Rn_g$  and obtain the mode group indices of  $n_g = 3.52, 3.47,$  and  $3.49$  from the observed mode wavelength intervals. Single-mode operation indicates that the mode coupling is not influenced by the size mismatch of the circular resonators caused by imperfect fabrication process. In fact, coupled microcavities with a large mismatch of cavity size will result in lasing spectra with two set of modes.

Finally, mode characteristics were investigated by two-dimensional (2D) FDTD simulation for coupled-circular microlasers with a middle bus waveguide confined by

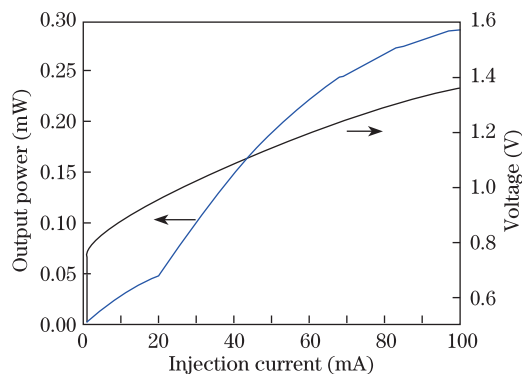


Fig. 2. Output power and applied voltage versus CW injection current at room temperature for a coupled-circular microlaser with a radius of  $10\ \mu\text{m}$ .

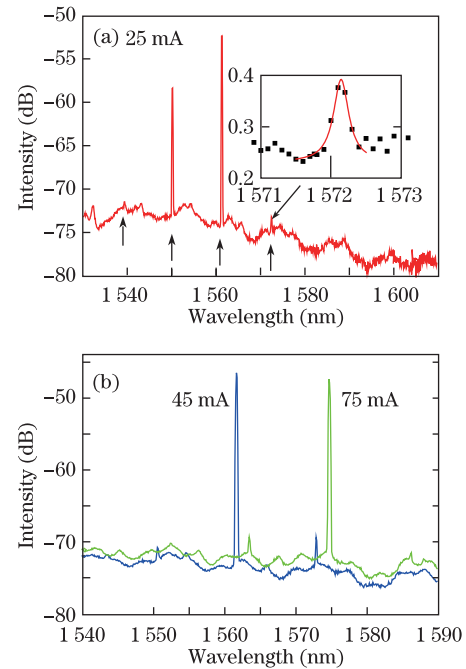


Fig. 3. Lasing spectra of the laser at the injecting currents of (a) 25, (b) 45, and 75 mA at room temperature. The inset shows the minor peak at 1572.14 nm fitted by Lorentzian function.

insulator  $\text{SiO}_2$  and  $p$ -electrode Ti and Au layers. In the simulation, the radius of coupled-circular and the width of the output waveguide were taken to be 3 and  $0.4\ \mu\text{m}$ , whereas the thicknesses of the  $\text{SiO}_2$ ,  $p$ -electrode Ti, and Au layers were 0.45, 0.04, and  $0.02\ \mu\text{m}$ , respectively. The effective refractive index of the laser wafer was taken to be 3.2, and the refractive indices of the  $\text{SiO}_2$ ,  $p$ -electrode Ti, and Au layers were 1.45,  $3.7 + 4.5i$ , and  $0.18 + 10.2i$ <sup>[12]</sup>, respectively. Because the active region comprises compressively strained multiple quantum wells, we consider TE modes in the numerical simulation. Gaussian modulated cosine impulse was used as the exciting source  $P(t) = \exp[-(t - t_0)^2/t_w^2]\cos(2\pi f_0 t)$  inside the resonator, where  $t_0$  is the pulse center,  $t_w$  is the pulse half width, and  $f_0$  is the center frequency of the pulse. A Courant time step of 0.0467 fs and a uniform mesh with the cell size of 20 nm were used in the simulation. In addition,  $t_0 = 2.39$  fs and  $t_w = 4.78$  fs were taken for a wide-band exciting source centered at  $f_0 = 200$  THz. The time-domain output of the  $z$ -direction magnetic field  $H_z$  was recorded at a selected monitor point inside the resonator as FDTD output. Then, Padé approximation was used to transform a late FDTD output from the time domain to the frequency domain<sup>[13]</sup>. The obtained intensity spectra for the coupled-circular microresonators laterally confined by  $\text{SiO}_2$  and  $\text{SiO}_2/\text{Ti}/\text{Au}/\text{air}$  are plotted as the solid and the dashed lines in Fig. 4, respectively. The mode  $Q$  factors decreased as the confined layer was transformed from  $\text{SiO}_2$  to  $\text{SiO}_2/\text{Ti}/\text{Au}/\text{air}$ .

Using a narrow-band exciting source with  $t_0 = 1.53$  ps and  $t_w = 3.06$  ps centered at a mode frequency, we simulate mode field patterns for the main peaks of the dashed line in Fig. 4 (i.e., for the resonator confined by  $\text{SiO}_2/\text{Ti}/\text{Au}/\text{air}$ ). Under the narrow-band exciting sources, the mode  $Q$  factors of  $3.0 \times 10^3$ ,  $2.2 \times 10^3$ ,

$8.6 \times 10^3$ ,  $2.8 \times 10^3$ ,  $1.2 \times 10^4$ ,  $3.3 \times 10^3$ ,  $4.0 \times 10^3$ , and  $1.1 \times 10^4$  were obtained for the modes at 197.96, 200.39, 203.24, 206.06, 208.50, 211.71, 212.18, and 213.75 THz, respectively. The obtained mode  $Q$  factors were approximately from 30% to 50% larger than those obtained from the multiple-mode intensity spectra in Fig. 4. We expect the mode  $Q$  factors obtained under narrow-band exciting sources to be more exact than those obtained under a wide-band exciting source. The obtained magnetic field patterns are plotted in Fig. 5 at the mode frequencies of 211.71, 212.18, and 213.75 THz. The field pattern in Fig. 5(a) is the third-order WGM  $TE_{28,3}$  and symmetry relative to the bus waveguide, which is much stronger coupled to the bus waveguide than that in Figs. 5(b) and (c). The mode field patterns in Figs. 5(b) and (c) are coupled modes  $TE_{28,3} + TE_{32,2}$ , and  $TE_{37,1} + TE_{32,2}$ , which are antisymmetric relative to the bus waveguide. Based on simulated mode field patterns, we can also assign the peaks at 197.96, 200.39, 203.24, 206.06, and 208.50 THz of the solid line in Fig. 4 as  $TE_{34,1} + TE_{29,2}$ ,  $TE_{26,3}$ ,  $TE_{35,1} + TE_{30,2}$ ,  $TE_{27,3}$ , and  $TE_{36,1} + TE_{31,2}$ . Here,  $TE_{v,m}$  is WGM with  $v$  and  $m$  the angular and radial mode numbers, respectively, and  $TE_{v_1,m_1} + TE_{v_2,m_2}$  is a coupled mode between  $TE_{v_1,m_1}$  and  $TE_{v_2,m_2}$ <sup>[14]</sup>. The coupled modes at 197.96, 203.24, and 208.50 THz are also coupled modes between the first- and the second-order WGMs with  $v_1 - v_2 = 5$ , having

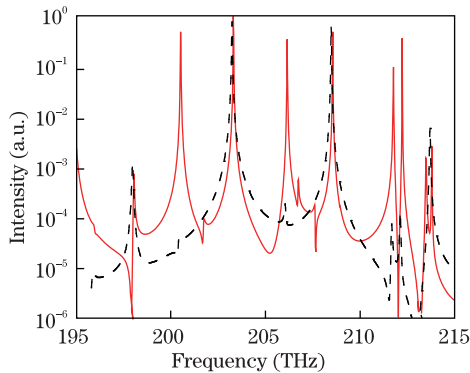


Fig. 4. Intensity spectra plotted as the solid and the dashed lines for the coupled-circular resonator laterally confined by  $SiO_2$  layer and  $SiO_2/Ti/Au$  layer, respectively, with the radius of  $3 \mu m$  and the width of the bus waveguide of  $0.4 \mu m$ .

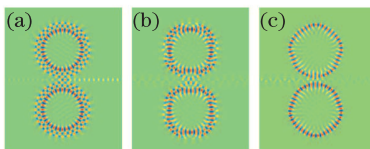


Fig. 5. Field patterns of the  $z$ -directional magnetic field component for the modes at the frequencies of (a) 211.71, (b) 212.18, and (c) 213.75 THz in the coupled-circular resonators with the middle bus waveguide.

similar mode field patterns as Fig. 5(c). The higher-radial-order WGMs are less affected by the roughness of circular perimeter than the first-order WGM; therefore, realizing independent clockwise and counter-clockwise traveling wave operations from the higher radial order WGMs is easy because the low-radial-order WGMs have low  $Q$  factors in the coupled-circular resonator.

In conclusion, we fabricate AlGaInAs/InP coupled-circular microlasers with a middle bus waveguide, and investigate output characteristics for a coupled-circular microlaser with radius of  $10 \mu m$ . Clear angular-mode spectra are observed with the angular mode wavelength interval of approximately 11 nm and mode  $Q$  factor of  $6.2 \times 10^3$  is obtained from the width of resonant peak. Furthermore, the numerical results show that the high- $Q$  confined modes in the coupled-circular resonator are mainly the symmetric WGMs and antisymmetric coupled WGMs relative to the bus waveguide.

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